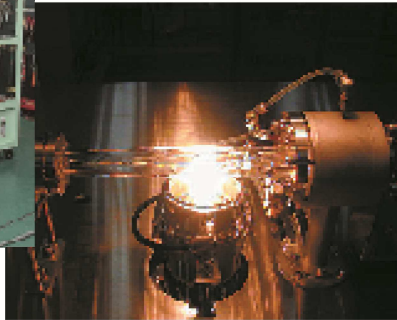


Liquid delivery MOCVD system

MPC1100V



Liquid delivery MOCVD system (MPC1100V) supplied to National Institute of Advanced Industrial Science and Technology



- Reactor : Horizontal type, Made of quartz
- Substrate size : $1 \times \phi 1''$
- Substrate heating : Lamp heating type
- Maximum heating : 800°C temperature (T.C. Value for control)
- Flow control : Liquid mass flow control
- Vaporizer : Heating type
- Applications : Oxidize, etc.

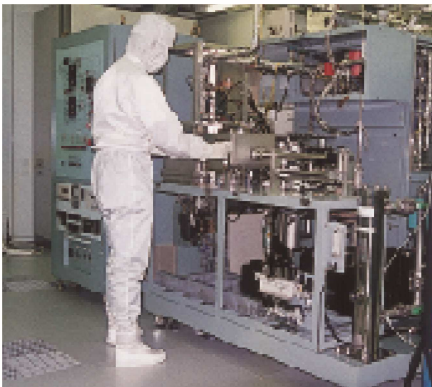
MPC2100H



Liquid delivery MOCVD system (MPC2100H) supplied to National Institute of Advanced Industrial Science and Technology

- Reactor : Vertical type, Made of stainless steel
- Substrate size : $1 \times \phi 2''$
- Substrate heating : Resistance heating type
- Maximum heating : 800°C (T.C. Value for control) temperature
- Flow control : Liquid mass flow control
- Vaporizer : Heating type
- Applications : Oxidize, etc.

MPC6100



Liquid delivery MOCVD system (MPC6100) supplied to Nara Institute of Science and Technology

- Reactor : Vertical type, Made of stainless steel
- Load-lock system : With transfer rod
- Substrate size : $1 \times \phi 6''$
- Substrate heating : Resistance heating type
- Maximum heating : 800°C (T.C. Value for control) temperature
- Flow control : Liquid mass flow control
- Vaporizer : Heating type
- Applications : Oxidize including PZT, etc.